

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2002-336675

(43)Date of publication of application : 26.11.2002

(51)Int.Cl.
 B01J 3/00
 B01J 3/02
 B08B 5/00
 B08B 7/00
 G02F 1/13
 G02F 1/1333
 H01L 21/304

(21)Application number : 2001-148194

(71)Applicant : DAINIPPON SCREEN MFG CO LTD
 KOBE STEEL LTD

(22)Date of filing : 17.05.2001

(72)Inventor : MIZOBATA IKUO
 MURAOKA YUSUKE
 SAITO KIMITSUGU
 KITAKADO RYUJI
 INOUE YOICHI
 SAKASHITA YOSHIHIKO
 WATANABE KATSUMITSU
 YAMAGATA MASAHIRO

(54) APPARATUS AND METHOD FOR TREATING UNDER HIGH PRESSURE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide an apparatus and a method for treating a substrate under high pressure, in which the substrate can be treated by using a pure processing fluid so that the atmospheric component intruded into a treating tank when the substrate is placed is not made to flow in a fluid producing/recovering system.

SOLUTION: Valves V1, V2, V3, V4 and V6 are closed and only a valve V5 is opened when the door of a substrate cleaning tank 5 is opened for placing the substrate so that gaseous carbon dioxide is supplied to the tank 5 and the tank 5 is purged for preventing the atmospheric component from intruding into the tank 5. Next, the door of the tank 5 is closed and the valve V6 is opened at the same time to form a venting line of the tank 5 so that the gas existing in the tank 5 and its surrounding pipes is pushed out to the atmosphere by the supplied gaseous carbon dioxide and the tank 5 is purged so that the atmospheric component to intrude into the tank 5 and its surrounding pipes by some rare accident does not stay behind. Then, the substrate is cleaned by using supercritical carbon dioxide.

